ABSTRACT

The present disclosure provides a semiconductor process apparatus and an exhaust gas treatment device thereof. The exhaust gas treatment device includes a housing, a flow guide member, and an adsorption member, where the housing includes an inlet and an outlet, and the inlet is configured to introduce, into the housing, process gas exhausted from a reaction chamber; the flow guide member is arranged in the housing, and partitions an interior of the housing into fluid channels, the fluid channels include an inflow channel and an outflow channel that communicate with the inlet and the outlet respectively, and the inflow channel communicates with the outflow channel; and a portion of the adsorption member is arranged in the inflow channel, the remaining portion of the adsorption member is arranged in the outflow channel, and the adsorption member is configured to adsorb a by-product in the process gas. The process gas flows through the inflow channel and the outflow channel sequentially, and the adsorption member absorbs the by-product in the process gas during flow of the process gas. The flow guide member increases flow resistance and a flow path of the process gas, prolongs residence time of the process gas in the housing, and makes the adsorption member fully absorb the by-product in the process gas. Thus, an absorption rate of the by-product is improved.

FIG. 1